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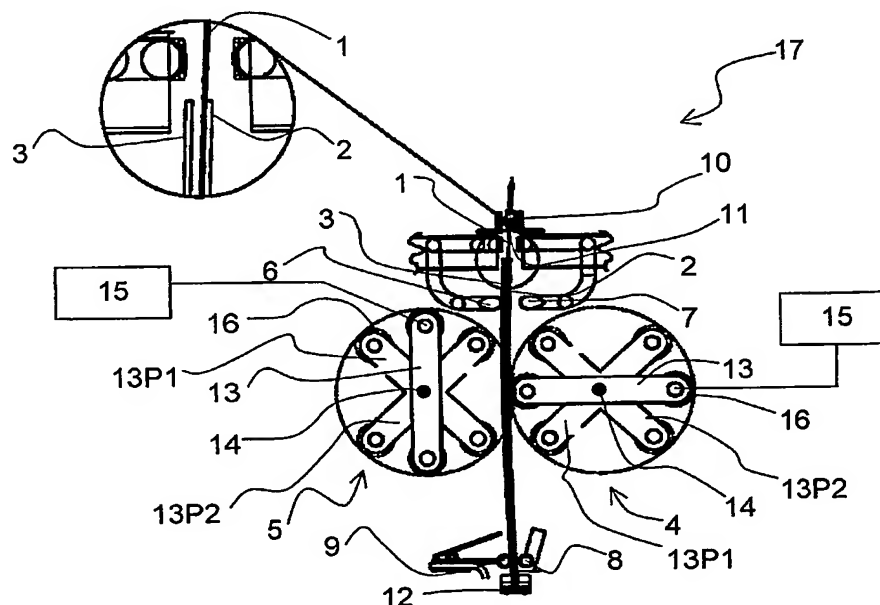
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[Continued on next page]

(54) Title: EQUIPMENT AND METHOD FOR REMOVING DEPOSITS CREATED IN ELECTROLYTIC REFINING



(57) Abstract: The invention relates to an equipment (4, 5) for removing deposits accumulated in electrolytic refining on the surface of an electrode, such as a cathode (1), said equipment including at least one element for stripping the deposits (2, 3) and at least one element for controlling the stripping element; said equipment includes at least one stripping element (13) that is turnably movable in the vertical direction of the cathode, and the cathode can be bent owing to the contact with said stripping element. The invention also relates to a method realized by said equipment.

WO 2005/054546 A1

**Declarations under Rule 4.17:**

- *as to applicant's entitlement to apply for and be granted a patent (Rule 4.17(ii)) for the following designations* AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, UZ, VC, VN, YU, ZA, ZM, ZW, *ARIPO patent* (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), *Eurasian patent* (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), *European patent* (AT, BE,

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